

ILLUMINATION SYSTEM AND METHOD ALLOWING FOR VARYING OF BOTH FIELD HEIGHT AND PUPIL

ABSTRACT OF THE DISCLOSURE

A method and system allow for changing (continuously or variably) both a field height and pupil of a beam that illuminates an object field. In one example, the object field can have a pattern generator (e.g., one or more reticles, spatial light modulators, or the like) positioned therein. The system and method for changing both the field height and the pupil can include a field defining element, a pupil defining element, and first and second zoom systems. The field defining element (FDE) can generate a field height of an illumination beam. The first zoom system can allow for changing of the field height of the illumination beam. The pupil defining element (PDE) can generate a pupil of the illumination beam. The second zoom system can allow for changing of the pupil of the illumination beam.

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